

# 3rd Announcement

The 28th Symposium on Photomask and Next Generation Lithography Mask Technology

# Photomask Japan 2022 Digital Forum

**April 26(Tue.) - 28(Thu.), 2022**

Considering the ongoing situation of COVID-19, we have concluded we will not be able to take sufficient safety measures at an in-person symposium. Photomask Japan 2022 will be held fully online on April 26-28.

We appreciate your understanding.

Symposium Chair: Prof. Takeo Watanabe, University of Hyogo (Japan)

Organized by Photomask Japan and SPIE, Co-organized by BACUS and EMLC

Organized by



**SPIE.**

Co-organized by



Supported by



## Program

Latest Program <https://www.photomask-japan.org/program.html>

**Keynote Speakers: Mr. Jed H. Rankin (GlobalFoundries) Mr. Srinivas Raghvendra (Synopsys) Mr. Yoshihiro Tezuka (Intel)**

The program is subject to change without notice.

April 26 (Tue.)			April 27 (Wed.)			April 28 (Thu.)		
PDT UTC-7	CEST UTC+2	JST UTC+9	PDT UTC-7	CEST UTC+2	JST UTC+9	PDT UTC-7	CEST UTC+2	JST UTC+9
		Digital Forum			Digital Forum			Digital Forum
25-Apr	26-Apr	8:00 - 8:10 <b>Opening</b>	26-Apr	27-Apr	8:00 - 8:50 <b>Session 8</b>	27-Apr	28-Apr	8:00 - 9:20 <b>Session 13</b>
16:00	1:00	8:10 - 9:10 <b>Session 1</b>	16:00	1:00	Opening Session: Day 2	16:00	1:00	Opening Session: Day 3
17:10	2:10	Opening Session: Day 1	16:50	1:50	- EDA -	17:20	2:20	- EUV & Industry Trend -
		9:10 - 9:30 Break			8:50 - 9:10 Break			9:20 - 9:40 Break
17:30	2:30	9:30 - 10:10 <b>Session 2</b>	17:10	2:10	9:10 - 10:40 <b>Session 9</b>	17:40	2:40	9:40 - 11:10 <b>Session 14</b>
18:10	3:10	EUV from U.S.			Curvilinear Data Handling			Inspection & Metrology
		10:10 - 10:30 Break	18:40	3:40	10:40 - 11:00 Break	19:10	4:10	11:10 - 11:30 Break
18:30	3:30	10:30 - 11:30 <b>Session 3</b>			11:00 - 12:20 <b>Session 10</b>	19:30	4:30	11:30 - 12:10 <b>Session 15</b>
19:30	4:30	Special Session	19:00	4:00	Defect Control	20:10	5:10	FPD
		- EUV Mask Blanks -			& Resolution			12:10 - 13:10 Lunch Break
		11:30 - 13:00 Lunch Break	20:20	5:20	12:20 - 13:20 Lunch Break			12:10 - 13:10 Lunch Break
21:00	6:00	13:00 - 14:30 <b>Session 4</b>			13:20 - 15:00 <b>Session 11</b>	21:10	6:10	13:10 - 14:30 Panel Discussion
		NIL 1	21:20	6:20	Poster Session			- SDGs and Carbon Neutral in
22:30	7:30	14:30 - 14:50 Break			[ Zoom Breakout Rooms ]	22:30	7:30	Semiconductor Manufacturing:
		14:50 - 16:10 <b>Session 5</b>	23:00	8:00	15:00 - 15:20 Break			what can PMJ do for the Earth? -
		NIL 2			15:20 - 17:20 Sponsor Session			14:30 - 14:50 Break
22:50	7:50	16:10 - 16:30 Break	23:20	8:20	17:20 - 17:40 Break	22:50	7:50	14:50 - 16:20 <b>Session 16</b>
		16:30 - 17:30 <b>Session 6</b>			17:40 - 19:10 <b>Session 12</b>			Metrology & MPC
26-Apr	9:10	EUV for High NA	27-Apr	10:20	EUV Tools	28-Apr	9:20	16:20 - 16:40 Break
0:10	9:10	17:30 - 17:50 Break	27-Apr	1:20		0:20	9:20	16:40 - 18:10 <b>Session 17</b>
0:30	9:30	17:50 - 19:00 <b>Session 7</b>						Writing Tools
		EUV Technologies	1:40	10:40		0:40	9:40	18:10-18:20 Closing
1:30	10:30							
1:50	10:50		3:10	12:10		2:20	11:20	
3:00	12:00							

For more information, contact:

**Photomask Japan Secretariat**

c/o JTB Communication Design, Inc.

Celestine Shiba Mitsui Bldg., 3-23-1 Shiba, Minato-ku, Tokyo 105-8335, Japan

E-mail : pmj@jtbcom.co.jp

<https://www.photomask-japan.org>

### Sponsor Session April 27 (Wed.) 15:20- 17:20 JST

CyberOptics Corporation

HORIBA, Ltd.

TOOL Corporation

Mycronic Technologies Corporation

ADVANCED TECHNOLOGIES CO., LTD.

For registration details, please see <https://www.photomask-japan.org/registration.html>